



IN THE OFFICE OF THE PATENT AND TRADEMARK OFFICE.

1. (Previously Presented) A lens arrangement for the particle-optical imaging of an object, to be imaged and positionable in an object area, into an image area, comprising:

a first focusing lens device for providing a field having a focusing effect on the imaging particles for imaging the object from the object area into an intermediate image area,

a second focusing lens device for providing a further field having a focusing effect on the imaging particles for imaging the object, which has been imaged into the intermediate image area, into the image area, and

a deflection lens device for providing a field having a deflecting effect on the imaging particles in a region of the intermediate image area.

2. (Previously Presented) The lens arrangement according to claim 1, wherein the field of the first focusing lens device comprises at least one field selected from the group consisting of magnetic and electric field which is substantially axially symmetric in respect of a central beam of a bundle of beams.

3. (Previously Presented) The lens arrangement according to claim 1, wherein the field of the first focusing lens device comprises at least one field selected from the group consisting of two magnetic, electric dipole, and quadrupole field arrangements which are axially spaced apart from one another in respect of a central beam of a bundle of beams of the imaging particles.

4. (Previously Presented) The lens arrangement according to claim 1, wherein the field of the deflection lens device comprises a magnetic field which is substantially mirror-symmetric in respect of a plane jointly extending with a central beam of a bundle of beams of the imaging particles.

5. (Previously Presented) The lens arrangement according to claim 1, wherein the field of the deflection lens device comprises at least one field selected from the group consisting of magnetic and electric

dipole field which is oriented transverse to a central beam of a bundle of beams of the imaging particles.

6. (Currently Amended) The lens arrangement according to claim 1, wherein an aperture stop is provided in at least one diffraction plane ~~of the first focusing lens device and the second focusing lens device~~ between the object area and the image area.

7. (Previously Presented) The lens arrangement according to claim 1, further comprising a first driving means for the deflection lens device for adjusting a strength of the deflecting field thereof, and a second driving means for adjusting a strength of the focusing fields in at least one of the first focusing lens device and the second focusing lens device, wherein the first driving means changes the field strength of the deflection lens device substantially proportionally dependent upon an external magnitude and the second driving means changes the field strength of the first focusing lens device and the second focusing lens device, respectively, substantially quadratically dependent upon the external magnitude.

8. (Previously Presented) The lens arrangement according to claim 7, wherein the lens arrangement is provided for imaging a subfield of the object area which is spaced apart from the optical axis of the lens arrangement by a variable distance onto the image area, and wherein the external magnitude comprises the distance of the subfield from the optical axis.

9. (Previously Presented) The lens arrangement according to claim 8, wherein the field of the deflection device deflects pairs of different beams of the particle beams imaging the subfield at substantially equal angles.

10. (Previously Presented) The lens arrangement according to claim 8, further comprising an illumination device for illuminating merely the subfield of the object area and a third driving means for the

illumination device for driving the illumination device in order for the distance of the illuminated subfield from the optical axis to be changed.

11. (Previously Presented) The lens arrangement according to claim 8, wherein the image area and the object area each have a predetermined nominal shape, wherein the second driving means changes the strength of the deflecting field of the first and the second focusing device, respectively, such that a central region of the subfield is imaged substantially sharply onto the image area, and wherein the first driving means changes the strength of the deflecting field of the deflection lens device such that the peripheral regions of the subfield are also imaged substantially sharply onto the image area.

12. (Original) The lens arrangement of claim 11, wherein the shape of the object area is that of a plane.

13. (Previously Presented) Method for device manufacture, comprising: a photolithographic step, wherein the photolithographic step comprises the transfer of a pattern defined by a mask to a particle-sensitive substrate using a lens arrangement, the lens arrangement comprising:

a first focusing lens device for providing a field having a focusing effect on the imaging particles for imaging the object from the object area into an intermediate image area,

a second focusing lens device for providing a further field having a focusing effect on the imaging particles for imaging the object, which has been imaged into the intermediate image area, into the image area, and

a deflection lens device for providing a field having a deflecting effect on the imaging particles in a region of the intermediate image area;
and

wherein the mask is disposed in the object area and the substrate is disposed in the image area.

14. (Previously Presented) The lens arrangement according to claim 1, wherein the field of the second focusing lens device comprises at least one field selected from the group consisting of magnetic and electric field which is substantially axially symmetric in respect of a central beam of a bundle of beams.

15. (Previously Presented) The lens arrangement according to claim 1, wherein the field of the first and the second focusing lens device comprises at least one field selected from the group consisting of magnetic and electric field which is substantially axially symmetric in respect of a central beam of a bundle of beams.

16. (Previously Presented) The lens arrangement according to claim 1, wherein the field of the second focusing lens device comprises at least one field selected from the group consisting of two magnetic, electric dipole, quadrupole field arrangements which are axially spaced apart from one another in respect of a central beam of a bundle of beams of the imaging particles.

17. (Previously Presented) The lens arrangement according to claim 1, wherein the field of the first and the second focusing lens device comprises at least one field selected from the group consisting of two magnetic, electric dipole, and quadrupole field arrangements which are axially spaced apart from one another in respect of a central beam of a bundle of beams of the imaging particles.